

# ABSTRACT

A chemical amplification type resist composition  
5 comprising a specific benzenesulfonyldiazomethane containing  
a long-chain alkoxyl group at the 2-position on benzene ring  
has many advantages including improved resolution, improved  
focus latitude, minimized line width variation or shape  
degradation even on long-term PED, minimized debris left  
10 after coating, development and peeling, and improved pattern  
profile after development and is thus suited for  
microfabrication.